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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Applicant:

Chris E. Barns et al.

Serial No.: 10/629,127

Filed: July 29, 2003

For: Preventing Silicide Formation at  
the Gate Electrode in a Replacement  
Metal Gate Technology

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Art Unit: 2822

Examiner: Khanh B. Duong

Docket: ITL.1016US  
P16703

Assignee: Intel Corporation

Mail Stop **Amendment**  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

**REPLY TO PAPER NO. 20050207**

Sir:

In response to the office action mailed March 8, 2005, please amend the above-referenced patent application as follows:

Date of Deposit: May 17, 2005

I hereby certify under 37 CFR 1.8(a) that this correspondence is being deposited with the United States Postal Service as **first class mail** with sufficient postage on the date indicated above and is addressed to the Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450.

*Cynthia L. Hayden*  
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